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Redwood MicroSystems

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All the ideas that's fit to patent.
FERNANDEZ
& ASSOCIATES, LLP

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Pages: 3

From: James M. Harris, Ph.D., #52,995
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Message:

Mr. Dupuis,

An appointment at 8:30 am on Thursday, Feb. 16 would be most convenient.

Draft claims and talking points attached.

regards,

[CONFIDENTIAL & PROPRIETARY ATTORNEY-CLIENT PRIVILEGED COMMUNICATION]

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**Talking Points:**

- 1) Light emitted from the Sun waveguide will have a point focus due to the cone shape versus applicant's lens produces a "line of light" as opposed to a point of light from the Sun lens. A point focus has limited application.
- 2) Applicant has amended claim 25 to further distinguish the lens type apart from Sun's; please note that Sun et al. teach a lens physically smaller than the associated waveguide.
- 3) Sun et al. teach one basic method of forming the lens which requires the cladding material surrounding the core waveguide, on all sides, to have an etch rate faster than the core material.
- 4) Please note in the last line of Examiner's ¶ 12, indicating the "teaching" of silicon as a substrate. Silicon, and "ceramics", without a cladding material, is unacceptable as a substrate as the etch rate of silicon in 49% HF is about 1 Å⁰ per minute, considerably slower than any type of doped glass; in buffered HF the Si etch rate is even slower. Note in Example 1 and 2 in the Sun specification the computed etch rate for cladding and core is about 3.5mm for 4.5 hours and 5.5 mm for 4 hours, respectively; this averages to about 180,000 Å⁰ per minute. Applicant asserts that the Sun et al. invention can not be practiced with silicon, or ceramics, functioning as a substrate and with no intervening lower cladding material.
- 5) Sun et al. invention can not be fabricated with a polymeric upper cladding; some polymers are resistant to HF etching and all polymers degrade above 500°C.
- 6) Ghoshal teaches a very specific class of polymers; application of the Ghoshal teaching to polymers not of his specific siloxane resin compositions may not result in a practical device.